

## WHAT IS CLAIMED IS:

1. A positive-working chemical-amplification photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) 100 parts by weight of a film-forming resinous compound having acid-dissociable solubility-reducing groups in the molecule and capable of being imparted with an increased solubility in an aqueous alkaline solution by interaction with an acid, which resinous compound is a copolymeric resin consisting of from 50 to 85% by moles of the monomeric units of hydroxystyrene, from 10 to 30% by moles of the monomeric units of styrene and from 2 to 20% by mols of the monomeric units of a tert-alkylacrylate or methacrylate;

(B) from 1 to 20 parts by weight of an acid-generating compound which is an onium salt compound having a fluoroalkylsulfonate as the anionic constituent;

(C) from 0.01 to 5 parts by weight of a phosphorus-containing oxo acid, and

(D) an amine selected from the group consisting of secondary amines and tertiary amines, in an amount sufficient to exhibit a quenching effect.

2. The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the tert-alkyl acrylate or methacrylate is tert-butyl acrylate or methacrylate.

3. The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the amount of the phosphorus-containing oxo acid as the

component (C) is in the range from 0.1 to 2.0 parts by weight per 100 parts by weight of the component (A).

4. The positive-working chemical-amplification photoresist composition according to claim 1 wherein the amine is triethylamine, tributylamine, dibutylamine or triethanolamine.